#### VOLtA: <u>V</u>oltage <u>O</u>ver-scaling Based <u>Lightweight</u> <u>A</u>uthentication for IoT Applications

Md Tanvir Arafin, Mingze Gao, and Gang Qu University of Maryland, College Park

{marafin, mgao1, gangqu}@umd.edu





device, user, data, and process shSec Lab

### Voltage Over-Scaling

\* Reducing V<sub>dd</sub> for power reduction
P=P<sub>stat</sub>+P<sub>dyn</sub>=C<sub>eff</sub>V<sub>dd</sub><sup>2</sup>f+V<sub>dd</sub>(I<sub>sub</sub>+I<sub>gate</sub>)
Quadratic dependence of power to V<sub>dd</sub>
\* Critical Voltage
Cell delay  $d_{gate} \sim V_{dd} / \beta (V_{dd} - V_t)^{\alpha}$ \* Scaling below critical voltage
Error due to path delay
Incorrect computation



Figure 1: Impact of voltage scaling on path delay distribution. Mean and sigma of delay distribution and number of paths failing to meet target delay increase (80-core processor in 65nm [2]).

Han et

al FTS'13

## VOS for DRAM Deanonymization

#### # Key idea:

- Use DRAM at a lower voltage
- Cell decay rate is a function of process variation
- Lowering V<sub>dd</sub> will create errors in the data
- Similar error pattern on the same chip
- Profile the error for deanonymizing DRAMs









Figure 2: DRAM fingerprints on data

Dr. Gang Qu (gangqu@umd.edu)

Rahmati et al. ISCA'15

#### Motivation of the Work

# Fabrication variation impacts VOS

- Transistor size shrinking makes V<sub>t</sub> variation wider  $\sigma_{\Delta Vt} = A_{\Delta Vt} / (WL)^{1/2}$
- Path delay error is a function of process variation
  - $d_{gate} \propto V_{dd} / \beta (V_{dd} V_t)^{lpha}$
- $\rightarrow$  observe ( $V_t$ ) variation by VOS?!
- Variation is believed to be unique, random, unclonable
- # Security applications
  - Device fingerprint/identifier
  - Device authentication
  - Hardware PUF and other security primitives



Challenges

### Where to Apply VOS?

- # The circuit/device: simple, but ...
- # Small and common building blocks
- # Existing VOS studies on different adders
  - Ripple Carry Adder
  - Carry Look ahead Adder
  - Han-Carlson Adder



Figure 3: Error Distribution for Different Adders [7]

Dr. Gang Qu (gangqu@umd.edu) Venkatesan et al. ICCAD'11

## VOS on Adders

All inputs are equi-probable
Error probability increase with scaling
Output error depends on both current input and the previous input



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### VOS Errors on RCA

#### # Why RCA?

- One of the simplest designs
- Error probability is higher with scaling
- Show our proposed ideas only
- 8-bit for reduced simulation time
- #Goals of the experiment
  - Uniqueness
  - Robustness



### Experimental Setup

# HSpice platform with FreePDK 45nm libraries # 200 modified NMOS and PMOS models with a  $\pm 7.5\%$  standard variation in V<sub>+</sub> # NMOS and PMOS transistor models are randomly chosen to build 100 different versions of each cell standard cell library. # Circuits designed in Verilog and synthesized with Cadence Virtuoso RT compilér. The synthesized design is converted into an HSpice netlist with standard cells randomly chosen from the modified library



### Experimental Parameters

Parameter Name	Value(s)				
Supply voltage $(V_{DD})$	0.4V/0.45V/1V				
NMOS threshold voltage $(V_{tn})$	$0.322 \pm 0.02415 V$				
PMOS threshold voltage $(V_{tp})$	$-0.302 \pm 0.02265 V$				
Operating temperature (T)	25 deg. C				
Clock Period $(T_{clk})$	1ns				



### Uniqueness of Error under VOS

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	A1	A2	A3	A4	A5	A6	A7	<b>A8</b>
A1	0	18.82	18.24	18.04	19.44	18.38	18.33	17.52
A2	18.82	0	5.36	5.21	5.67	5.65	3.89	5.39
A3	18.24	5.36	0	4.62	5.98	5.11	5	6.79
A4	18.04	5.21	4.62	0	5.73	3.53	4.13	6.44
A5	19.44	5.67	5.98	5.73	0	6.04	5.59	6.28
A6	18.38	5.65	5.11	3.53	6.04	0	4.96	6.64
A7	18.33	3.89	5	4.13	5.59	4.96	0	5.41
A8	17.52	5.39	6.79	6.44	6.28	6.64	5.41	0

Table 1. Pairwise Hamming distance (in percent) between the output from 8 devices at 0.4V.

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#### Robustness with $V_{dd}$ Variation

 With voltage increases
 Error probability decreases

 Output converges to the correct value
 Noise in V<sub>dd</sub> can have detrimental effect



Figure 7. Hamming distance (in percent) between devices at 0.45V.

#### Robustness with Temperature Variation

 Error distribution is temperature sensitive
 No. of bit flips is relatively small with small temperature variations



Figure 8. Temperature dependent bit flips for two different adders. The distance is calculated from the results produced at T=25 degree Celsius. The blue (left) bar represents the temperature dependent bit-flip for adder A2 and the yellow (right) bar represents the adder A3. Dr. Gang Qu (gangqu@umd.edu) 1

# VOLtA: Protocol

#### # Registration

- Bob has a password K=(k1, k2)
- Alice registers K=(k1, k2), and profiles or models the error pattern M.

#### # Authentication

- Alice picks a random string R and sends it to Bob.
- Bob calculated L=R+k1 using the adder and then calculates Y=L ⊕ k2 =(R+k1) ⊕ k2.
- Bob sends Y to Alice.
- Alice calculates L=Y ⊕ k2 and L'=M(R,k1). If distance (L',L) < threshold, Bob is authenticated.</p>

**A**e

# VOLtA: Analysis

- # Effectiveness
  # Choice of Key
  # Attacks
  # Random Guessing
  # Eavesdropping
  # Side-channel Attack
  - Learning Attack







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Figure 6. A histogram of the Euclidian distances (a) between the figures 5(a) and 5(b); (b) between the figures 5(a) and 5(c); between the figures 5(b) and 5(c)

#### Conclusions

- Hardware for lightweight security in IoTVoltage Over-Scaling
  - A popular approximate computing method
  - Leaves a process variation dependent device signature in the approximate results
  - Drawbacks: information leak, deanonymization
  - → A new security primitive!
- **#** VOS based Device authentication
  - Lightweight: low cost, (low level of) security
  - Good for certain IoT applications



# Thank You!



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